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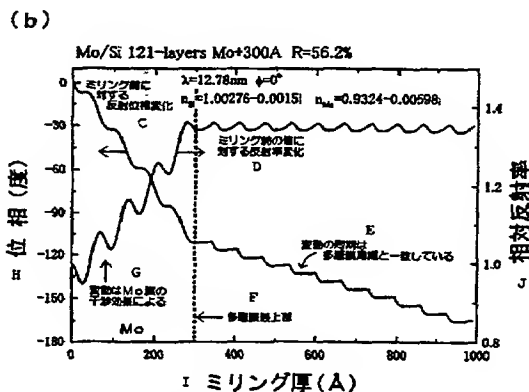
(54) 発明の名称: 多層膜反射鏡等の光学素子、その作成方法およびそれを用いた装置

(a)

↓ 上からけする A

Mo } 300Å

Mo/Si } 121層 B



- A...SCRAPE OFF FROM ABOVE
B...121 LAYERS
C...REFLECTION PHASE CHANGE FOR PRE-MILLING
D...REFLECTION FACTOR CHANGE FOR PRE-MILLING VALUE
E...VARIATION FREQUENCY AGREES WITH MULTILAYER FILM FREQUENCY
F...TOPMOST PORTION OF MULTILAYER FILM
G...VARIATION CAUSED BY INTERFERENCE EFFECT OF M_0 FILM
H...PHASE (DEGREES)
I...MILLING THICKNESS (Å)
J...RELATIVE REFLECTION FACTOR

(57) Abstract: A multilayer film reflection mirror capable of simply correcting a wavefront phase, and a production method therefor. A reflection mirror using reflection by a multilayer film, wherein the multilayer film is formed with a frequency higher than is necessary for a reflection factor to substantially saturate, and is scraped off according to a wavefront phase regulation amount of an outgoing light to thereby regulate a wavefront phase. Since a correction film and a multilayer film having a capability beyond a substantial saturation of a reflection factor are formed, correction is possible by scraping off the multilayer film even when a correction-film removing is not sufficient for phase correction, whereby more accurate phase correction is implemented.

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